

METHOD AND DEVICE FOR CHECKING LITHOGRAPHY DATA

Abstract

Devices and methods are provided that include advantages such as the ability

5 to identify sizes, shapes and locations of frequently unwanted additional features
that occur as a result of photolithographic interference. The additional feature
information is obtained through use of simulation methods with reduced processing
time or solving a system of equations. This allows a user to quickly find
information about additional feature printing before the features are printed, and

10 before the reticle is made.